



# Self-Turn-on-Free 5V Gate Driving for 1200V Scaled IGBT

著者	Tsukuda Masanori, Sudo Masaki, Hasegawa Kazunori, Abe Seiya, Saraya Takuya, Takakura Toshihiko, Fukui Munetoshi, Itou Kazuo, Suzuki Shinichi, Takeuchi Kiyoshi, Ninomiya Tamotsu, Hiramoto Toshiro, Omura Ichiro
journal or publication title	2019 31st International Symposium on Power Semiconductor Devices and ICs (ISPSD)
year	2019-05-22
URL	<a href="http://hdl.handle.net/10228/00007305">http://hdl.handle.net/10228/00007305</a>

doi: [info:doi/10.1109/ISPSD.2019.8757665](https://doi.org/10.1109/ISPSD.2019.8757665)

# Self-Turn-on-Free 5V Gate Driving for 1200V Scaled IGBT

Masanori Tsukuda<sup>\*†</sup>, Masaki Sudo<sup>†</sup>, Kazunori Hasegawa<sup>†</sup>, Seiya Abe<sup>†</sup>, Takuya Saraya<sup>‡</sup>, Toshihiko Takakura<sup>‡</sup>, Munetoshi Fukui<sup>‡</sup>, Kazuo Itou<sup>‡</sup>, Shinichi Suzuki<sup>‡</sup>, Kiyoshi Takeuchi<sup>‡</sup>, Tamotsu Ninomiya<sup>\*</sup>, Toshiro Hiramoto<sup>‡</sup>, Ichiro Omura<sup>†</sup>  
 Email: tsukuda@life.kyutech.ac.jp

<sup>\*</sup>Green Electronics Research Institute, Kitakyushu, Fukuoka, Japan

<sup>†</sup>Kyushu Institute of Technology, Kitakyushu, Fukuoka, Japan

<sup>‡</sup>The University of Tokyo, Tokyo, Japan

**Abstract**—Negative biasing of the gate voltage in a scaled insulated gate bipolar transistor (IGBT) during the off-state was modeled and found to be effective against self-turn-on failures. The required self-turn-on-free criteria were verified experimentally.

**Keywords**—scaled IGBT, self-turn-on, gate shielding layer

## I. INTRODUCTION

This paper reports the modeling and demonstration of a self-turn-on-free 5V gate drive ( $V_{GE\_th} = 1.7$  V) for a 1200V scaled insulated gate bipolar transistor (IGBT), in which the MOS gate shielding layer prevents self-turn-on failures [1–3]. Since 2011, new IGBTs with a scaling (miniaturizing) factor of  $k = 3$  have been proposed and fabricated [4–6]. The scaled IGBT features a high conduction current capability and a low gate drive voltage of 5V. A low gate drive voltage dramatically reduces the gate drive power in proportion to the square of the voltage swing; that is, by a factor of  $k^2$ . However, it has the disadvantage of self-turn-on failures due to switching noise, especially when driven at high  $dV_{CE}/dt$  [7, 8], because of the low gate threshold voltage. In this paper, we first analyze the gate shielding mechanism and propose

gate voltage model for the planer gate IGBT. Then we demonstrate a shielding mechanism and present the criteria for a scaled trench gate IGBT that is free from self-turn-on failures.

## II. ANALYSIS OF THE MOS GATE SHIELDING MECHANISM

Off-state negative gate biasing has been employed for IGBT gate drives because it was believed that the negative voltage adds a margin to the gate threshold voltage, and thus

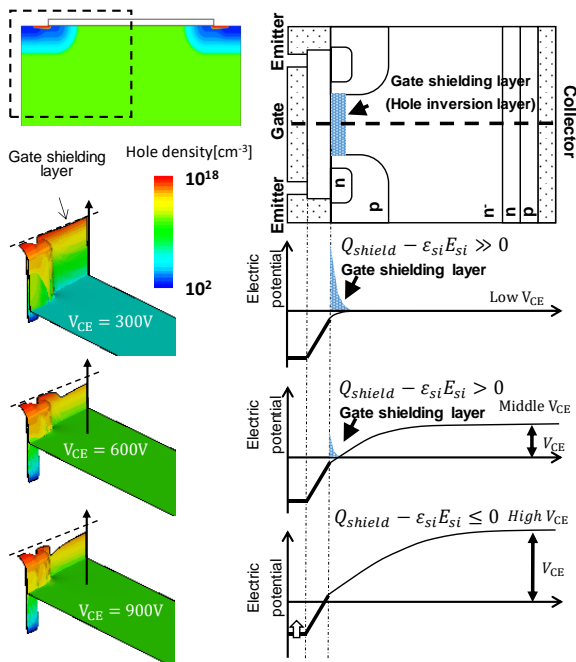


Fig. 1. TCAD simulation of a planar gate IGBT with a negative bias voltage and the electrostatic potential distribution in the device.

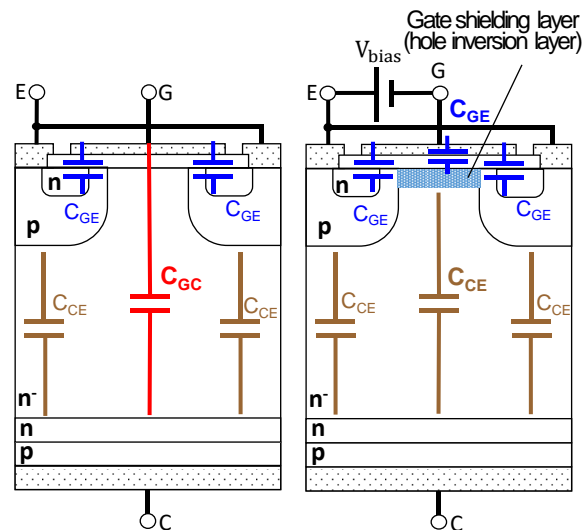


Fig. 2. Schematic view of parasitic capacitance in a planar IGBT with/without a gate shielding layer.

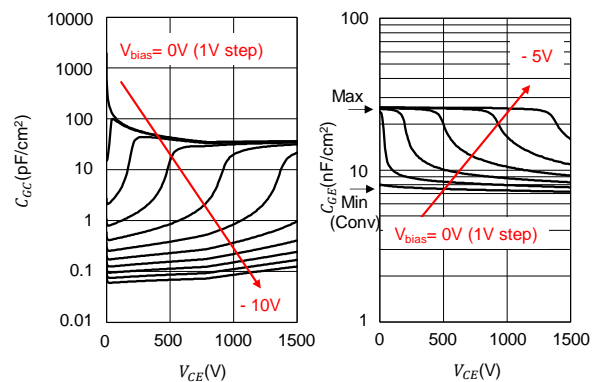


Fig. 3. TCAD simulation of  $C_{GC}$  and  $C_{GE}$  in a planar gate IGBT.

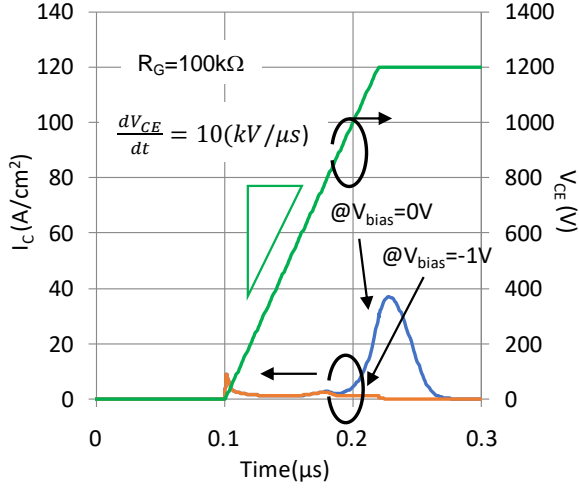


Fig. 4. TCAD simulation of the collector voltage and current waveforms during the off-state under high  $dV_{CE}/dt$  conditions for a planar gate IGBT.

reduces the self turn-on risk. Recently, it has been reported that a negative gate bias induces a shielding (hole inversion) layer beneath the MOS gate, so that the electric field when driven at high  $dV_{CE}/dt$  is completely terminated to the source/emitter voltage, and thus the MOS device is strongly protected from self-turn-on failures. However, the physics-based mechanism has not been explained or modeled.

A gate shielding layer appears with a negative gate bias at a low  $V_{CE}$ . This layer is removed at a high  $V_{CE}$  with the increase in the electric field in the N-base (N-drift) surface  $E_{si}$ , and this was confirmed TCAD simulation (Fig. 1). The layer appears when the initial ( $V_{CE}=0V$ ) shielding layer charge  $Q_{shield}$  is larger than the charge from  $V_{CE}$ . The shielding layer changes  $C_{GC}$ ,  $C_{GE}$  and  $C_{CE}$ .  $C_{GC}$  changes in a part of  $C_{CE}$  and  $C_{GE}$  appears between the MOS gate and the N-base (N-drift) surface. As a result,  $C_{GC}$  becomes very small and  $C_{CE}$  and  $C_{GE}$  become large (Figs. 2 and 3). We used TCAD to simulate the waveforms at a very high  $dV_{CE}/dt$  for an IGBT driven at  $10kV/\mu s$  in the off-state (Fig. 4). Applying a negative gate bias of  $-1V$  dramatically reduced the self-turn-on current.

### III. GATE VOLTAGE MODEL IN THE OFF-STATE

Gate voltage was modeled based on the shielding layer mechanism. When a shielding layer exists,  $V_{GE}$  can be expressed by the following equation, because  $C_{GE}$  is completely shielded by the shielding layer.

$$V_{GE}(Q_{shield} - \epsilon_{si}E_{si} > 0) = V_{bias} \quad (1)$$

where  $Q_{shield} = \epsilon_{ox}E_{ox} = \epsilon_{ox} \frac{V_{bias}}{t_{ox}}$

When no shielding layer exists (Fig. 5),  $V_{GE}$  is expressed by the following equation, because  $C_{GC}$  and  $C_{GE}$  are connected in series between the collector and emitter terminals via the gate terminal.

$$\int_{V_{CE,th}}^{V_{CE}} C_{GC} dV_{CE} = \int_{V_{bias}}^{V_{GE}} C_{GE} dV_{GE}$$

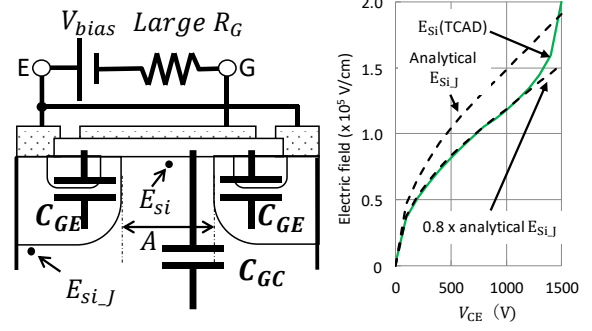


Fig. 5. Schematic of  $V_{GE}$  model of Eq. (2) and the electric field as a function of  $V_{CE}$  ( $E_{si} = \alpha E_{si,J}$ ,  $\alpha = 0.8$ ).

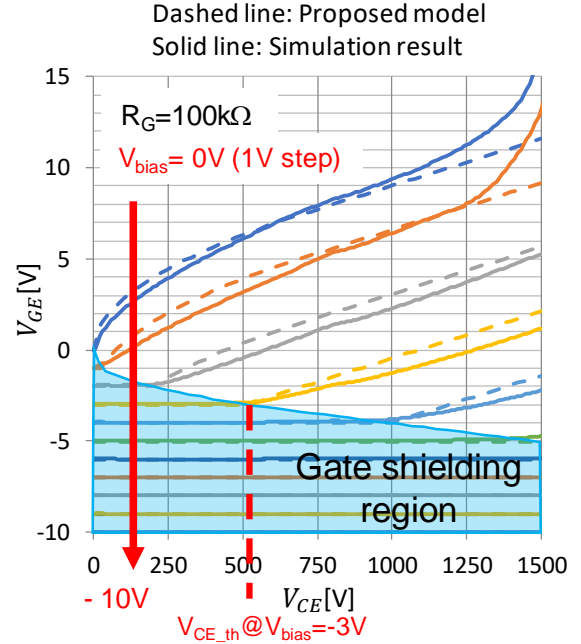


Fig. 6. Off-state  $V_{GE}$  calculated using the proposed model compared with the TCAD simulation results.

$$A(\epsilon_{si}E_{si} - Q_{shield}) = (V_{GE} - V_{bias})C_{GE}$$

$$V_{GE}(Q_{shield} - \epsilon_{si}E_{si} \leq 0) = V_{bias} + \frac{A(\epsilon_{si}E_{si} - Q_{shield})}{C_{GE}} \quad (2)$$

$$\text{where } E_{si} = \alpha E_{si,J} = \alpha \sqrt{\frac{2qN_B V_{CE}}{\epsilon_{si}}} \text{ or } \alpha \left( \frac{V_{CE}}{W_B} + \frac{qN_B W_B}{2\epsilon_{si}} \right)$$

The  $V_{GE}$  calculated from the analytical model was compared with the  $V_{GE}$  from the TCAD simulation. The values for  $V_{GE}$  were in close agreement, confirming the accuracy of the analytical model (Fig. 6).

### IV. SELF-TURN-ON-FREE CRITERIA FOR THE SCALED IGBT

The self-turn-on-free criteria for a scaled 1200V IGBT were confirmed experimentally. An IGBT with a gate drive voltage of 5V ( $k = 3$ ) was used as the DUT because we assumed that a low  $V_{GE,th}$  of 1.7 V would facilitate self-turn-on failures (Fig. 7). Measurement of  $C_{GC}$  and  $C_{GE}$  confirmed the appearance and disappearance of the gate shielding layer (Fig. 8).  $C_{GC}$  decreased on applying a negative bias voltage

with a low  $V_{CE}$ . Conversely,  $C_{GE}$  increased on applying a negative bias voltage. The characteristics agreed with those from the TCAD simulation analysis (Fig. 3). The value of

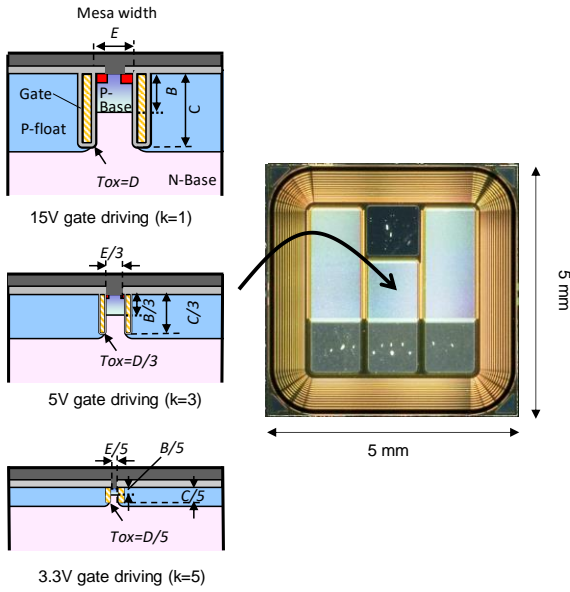


Fig. 7. Scaled IGBT and the fabricated 5V gate driving trench gate IGBT chip.

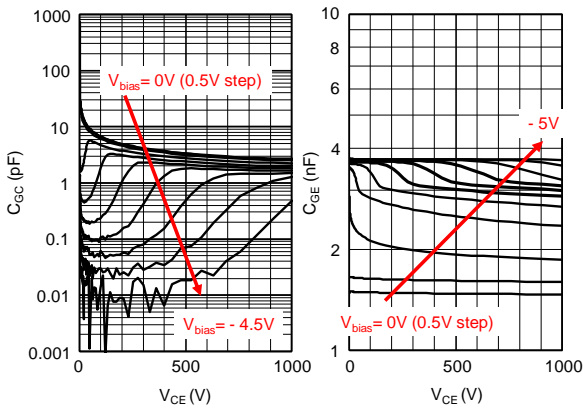


Fig. 8. Measured  $C_{GC}$  and  $C_{GE}$  for the 5V gate trench gate IGBT chip ( $C_{GC}$  was calibrated assuming that  $C_{GC}$  was 0F at  $V_{bias} = -5V$ ).

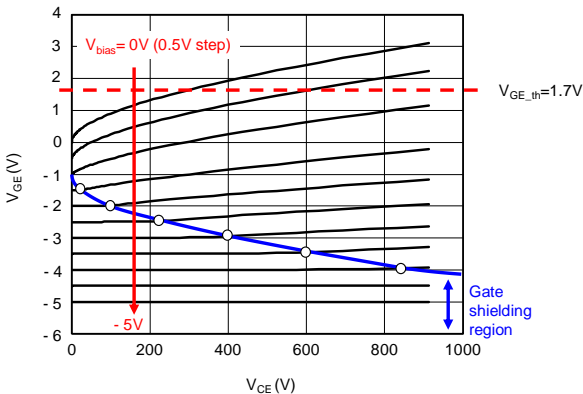


Fig. 9. Expected  $V_{GE}$  for the 5V gate driving IGBT chip from the measured  $C_{GC}$  and  $C_{GE}$  (Fig. 8).

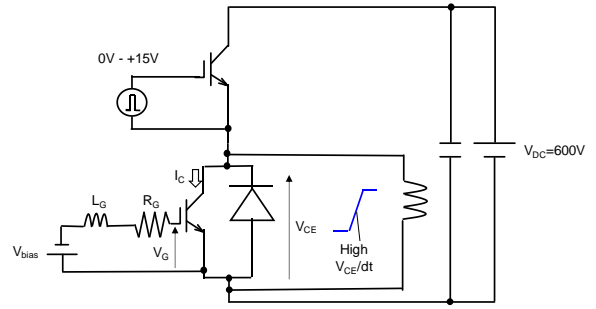


Fig. 10. Test circuit for self-turn-on-free driving (Inductive load and single pulse switching).

$V_{GE}$  was obtained from  $C_{GC}$  and  $C_{GE}$  using the following equation.

$$V_{GE} = V_{bias} + \frac{\int_0^{V_{CE}} C_{GC} dV_{CE}}{C_{GE}} \quad (3)$$

The results of the TCAD simulation and the model generally agreed well (Figs. 6 and 9). The required  $V_{bias}$  of  $-1V$  was expected from Eq. 3.

We confirmed experimentally that the scaled IGBT operated free from self-turn-on-failures in a single pulse test. The gate resistance of the switching IGBT was  $0\Omega$  for a high  $dV_{CE}/dt$  of  $25kV/\mu s$  (Fig. 10). Even under high impedance gate circuit conditions ( $L_G = 400nH$  and  $R_G$  up to  $1k\Omega$ ), no self-turn-on failures occurred when applying a negative gate bias of  $-2V$  or below (Fig. 11). The difference from the expected value of  $V_{bias}$  is assumed to be due to the short expansion of the depression layer with the high  $dV_{CE}/dt$ .

We also tried self-turn-on-free driving with no  $V_{bias}$  to simplify the gate drive circuit. With  $L_G$  as low as  $10nH$ , self-turn-on-free operation was established without a negative gate bias (Fig. 12). Thanks to the low impedance of the gate circuit, the charge on  $C_{GC}$  quickly discharged to the emitter terminal.

## V. CONCLUSION

We found by modeling and by experiment that a negatively biased gate voltage was effective against self-turn-on failures. Simple yet accurate model equations were proposed and the results showed good agreement with the TCAD simulation. The model can be easily implemented in a SPICE device model (see Appendix), and the parameters can be easily extracted from measurement and the N-base structure. The self-turn-on-free criteria we obtained by experiment demonstrated that completely self-turn-on-free operation is possible with a negative  $V_{bias}$  even for a  $1200V$  scaled IGBT with the gate driven at  $5V$ . The practicality of a gate drive voltage at a CMOS logic level of  $5V$  shows the possibility of new functionality for gate drives using digital IoT/AI technology [9].

## ACKNOWLEDGMENTS

This paper is based on the results obtained from a project commissioned by the New Energy and Industrial Technology Development Organization (NEDO) (P10022).

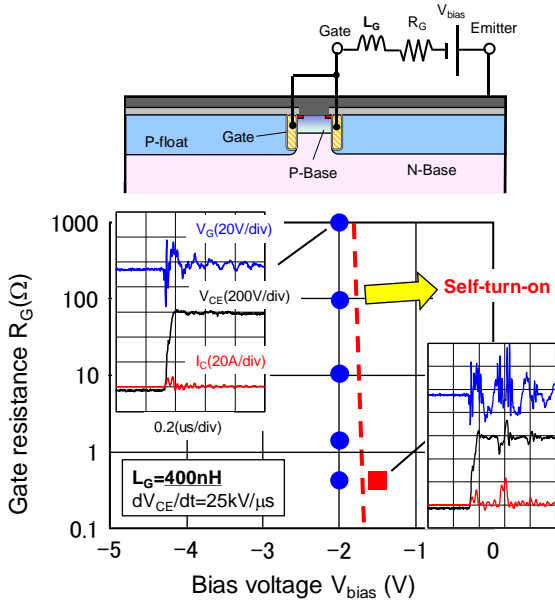


Fig. 11. Absolute criterion for self-turn-on-free driving for 1200V scaled trench gate IGBT and the waveforms.

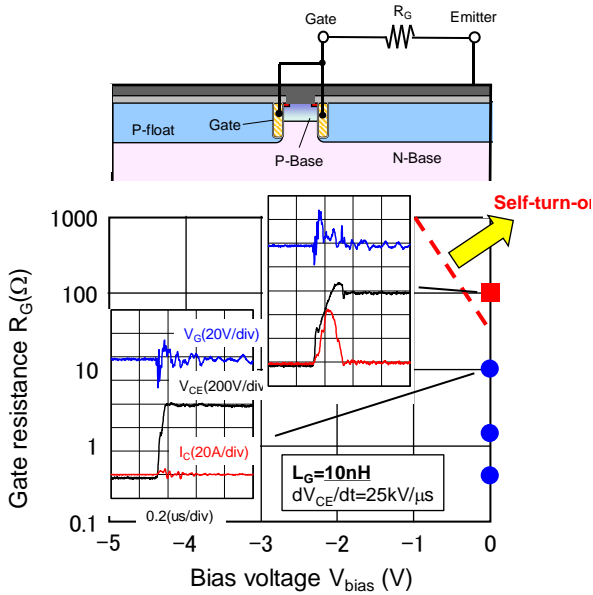


Fig. 12. Criteria for a low gate impedance for self-turn-on-free driving of a 1200V trench gate scaled IGBT and the waveforms.

#### REFERENCES

- [1] T. Nishiwaki, T. Hara, K. Kaganoi, M. Yokota, Y. Hokomoto, Y. Kawaguchi, "Design Criteria for Shoot-Through Elimination in Trench Field Plate Power MOSFET," Proc. of ISPSD'14, pp.382–385, 2014.
- [2] K. Murata, K. Harada, "Analysis of a Self Turn-on Phenomenon on the Synchronous Rectifier in a DC-DC Converter," Proc. of INTELEC, pp. 199–204, 2003.
- [3] B. Yang, S. Xu, J. Korec, J. Shen, "Design Considerations on Low Voltage Synchronous Power MOSFETs with Monolithically Integrated Gate Voltage Pull-down Circuitry," Proc. of ISPSD'12, pp. 121-124, 2012.

- [4] M. Tanaka, I. Omura, "Structure oriented compact model for advanced trench IGBTs without fitting parameters for extreme condition: Part I," Microelectronics Reliability 51, pp. 1933-1937, 2011.
- [5] K. Kakushima, T. Hoshii, K. Tsutsui, A. Nakajima, S. Nishizawa, H. Wakabayashi, I. Muneta, K. Sato, T. Matsudai, W. Saito, T. Saraya, K. Itou, M. Fukui, S. Suzuki, M. Kobayashi, T. Takakura, T. Hiramoto, A. Ogura, Y. Numasawa, I. Omura, H. Ohashi, H. Iwai, "Experimental verification of a 3D scaling principle for low V<sub>ce(sat)</sub> IGBT," Proc. of IEDM, pp. 10.6.1-10.6.4, 2016.
- [6] T. Saraya, K. Itou, T. Takakura, M. Fukui, S. Suzuki, K. Takeuchi, M. Tsukuda, Y. Numasawa, K. Satoh, T. Matsudai, W. Saito, K. Kakushima, T. Hoshii, K. Furukawa, M. Watanabe, N. Shigyo, K. Tsutsui, H. Iwai, A. Ogura, S. Nishizawa, I. Omura, H. Ohashi, T. Hiramoto, "Demonstration of 1200V Scaled IGBTs Driven by 5V Gate Voltage with Superiorly Low Switching Loss," Proc. of IEDM, 2018.
- [7] S. Abe, K. Hasegawa, M. Tsukuda, I. Omura, T. Ninomiya, "Modelling of the shoot-through phenomenon introduced by the next generation IGBT in inverter applications," Microelectronics Reliability 76-77, pp. 465-469, 2017.
- [8] M. Tsukuda, S. Abe, K. Hasegawa, T. Ninomiya, I. Omura, "Bias voltage criteria of gate shielding effect for protecting IGBTs from shoot-through phenomena," Microelectronics Reliability, Vol. 88-90, pp. 482-485, 2018.
- [9] K. Miyazaki, S. Abe, M. Tsukuda, I. Omura, K. Wada, M. Takamiya, T. Sakurai, "General-purpose clocked gate driver (CGD) IC with programmable 63-level drivability to reduce I<sub>c</sub> overshoot and switching loss of various power transistors," Proc. of APEC, pp. 2350-2357, 2016.

#### APPENDIX

We propose a configuration for the capacitances in the device for a SPICE device model (Fig. 13). The appearance and disappearance of the shielding layer is at the border of the capacitance value. The required  $V_{bias}$  is expressed by the following equation.

$$Required\ V_{bias} = \frac{\epsilon_{si} E_{si} t_{ox}}{\epsilon_{ox}} = \frac{\epsilon_{si} E_{si} A}{C_{GE\_max} - C_{GE\_conv}} \quad (4)$$

This SPICE model is applicable to all MOS gate devices.

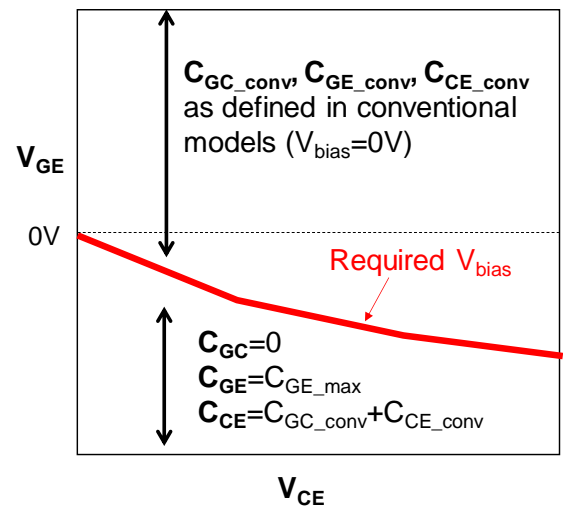


Fig. 13. Capacitance parameters for the SPICE device model from the gate shielding layer for MOS gate devices.